



**INFORMATION DISCLOSURE  
STATEMENT BY APPLICANT**

Form PTO-1449 (Modified)  
(Use several sheets if necessary)

Sheet

1

of

5

**COMPLETE IF KNOWN**

Application Number	10/631,376
Confirmation Number	2135
Filing Date	July 30, 2003
First Named Inventor	Eric J. BERGMAN
Group Art Unit	1746
Examiner Name	

Attorney Docket No. 54008.8033.US00 (P03-0004)

**U.S. PATENT DOCUMENTS**

Examiner Initials*	Cite No.	U.S. Patent or Application		Name of Patentee or Inventor of Cited Document	Date of Publication or Filing Date of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		NUMBER	Kind Code (if known)			
ZE	AB	4,695,327		Grebinski	09/22/87	
	AC	4,974,530		Lyon	12/04/90	
	AD	5,055,138		Slinn	10/08/91	
	AE	5,120,370		Mori et al.	06/09/92	
	AF	5,181,985		Lampert et al.	01/26/93	
	AG	5,232,511		Bergman	08/03/93	
	AH	5,234,540		Grant et al.	08/10/93	
	AI	5,235,995		Bergman et al.	08/17/93	
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	AK	5,248,380		Tanaka	09/28/93	
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	AN	5,415,191		Mashimo et al.	05/16/95	
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	AP	5,503,708		Koizumi et al.	04/02/96	
	AQ	5,520,744		Fujikawa et al.	05/28/96	
	AR	5,632,847		Ohno et al.	05/27/97	
	AS	5,647,386		Kaiser	07/15/97	
	AT	5,658,615		Hasebe et al.	08/19/97	
	AU	5,705,089		Sugihara et al.	01/06/98	
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	AY	5,803,982		Kosofsky et al.	09/08/98	
	AZ	5,858,107		Chao et al.	01/12/99	
	BA	5,896,875		Yoneda	04/27/99	
ZE	BB	5,911,837		Matthews	06/15/99	

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EL-Arini

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11/15/04

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[54008.8033.US00/LA041610.014]

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Z E	BC	5,944,907		Ohmi	08/31/99	
	BD	5,971,368		Nelson et al.	10/26/99	
	BE	6,299,696		Kamikawa et al.	10/09/01	
	BF	2002/0011257		DeGendt	01/31/02	
Z E	BG	6,551,409		DeGendt	04/22/03	

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		Office	NUMBER	Kind Code (if known)				
Z E	BH	EP	0 344 764		Wacker Chemitronic	1989-12-06		
	BI	EP	0 548 596		Chlorine Engineers Corp.	30.06.93		X
	BJ	EP	0 702 399		Siemens AG	1996-03-20		
	BK	GB	2 287 827		NEC Corporation	27.09.1995		X
	BL	JP	52-12063		Hitachi Ltd.	04.04.1977		X
	BM	JP	03-041729		Tokyo Electron Ltd.	22.02.1991		
	BN	JP	64-008630		Tokyo Electron Ltd.	12.01.1989		
	BO	JP	1189921		Mitsubishi Electric Corp.	1989-07-31		
	BP	JP	54-034751		Hitachi Ltd.	14.03.1979		
	BQ	JP	04-079221		Seiko Epson Corp.	12.03.1992		
Z E	BR	JP	61-004232		NEC Corp.	10.01.1986		

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Z E	BS	Alder, M., et al., "The Kinetics and Mechanism of Hydroxide Ion Catalyzed Ozone Decomposition in Aqueous Solution." <i>J. Am. Chem. Soc.</i> , 72:1884-1886 (1950).					
Z E	BT	Amick, J.A., "Cleanliness and the Cleaning of Silicon Wafers." <i>Solid State Technology</i> , pp. 47-52 (Nov. 1976).					

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ZE	BU	Anantharaman, et al., "ORGANICS: Detection and Characterization of Organics in Semiconductor DI Water Processes." <i>Ultrapure Water</i> , pp. 30-36 (Apr. 1994).			
	BV	Baumgärtner, H., et al., "Ozone Cleaning of the Si-SiO <sub>2</sub> System." <i>Appl. Phys. A</i> , 43:223-226 (1987).			
	BW	Bedge, S., et al., "Kinetics of UV/O <sub>2</sub> Cleaning and Surface Passivation: Experiments and Modeling." <i>Mat. Res. Soc. Symp. Proc.</i> , 259:207-212 (1992).			
	BX	Bolon, D.A., et al., "Ultraviolet Depolymerization of Photoresist Polymers," <i>Polymer Engineering and Science</i> , 12(2):108-111 (1972).			
	BY	Christenson, K., et al., "Deionized Water Helps Remove Wafer Stripping 'Resist'-ance." <a href="http://www.precisioncleaningweb.com--Precision Cleaning Web--Archives">www.precisioncleaningweb.com--Precision Cleaning Web--Archives</a> , pp. 10-20 (Apr. 1998).			
	BZ	Egitto, F.D., et al., "Removal of Poly (Dimethylsiloxane) Contamination From Silicon Surfaces With UV/Ozone Treatment." <i>Mat. Res. Soc. Symp. Proc.</i> , 385:245-250 (1995).			
	CA	Gabriel, C., et al., "Reduced Device Damage Using An Ozone Based Photoresist Removal Process." <i>SPIE Advances in Resist Technology and Processing VI</i> , 1086:598-604 (1989).			
	CB	Ganesan, G., et al., "Characterizing Organic Contamination in IC Package Assembly." <i>The Int'l. Soc. for Hybrid Microelectronics</i> , 17(2), Second Quarter, 152-160 (1994).			
	CC	Golland, D.E., et al., "The Clean Module: Advanced Technology for Processing Silicon Wafers." <i>Semiconductor Int'l.</i> , pp. 154-157 (Sep. 1987).			
	CD	Goulding, M.R., "The selective epitaxial growth of silicon," <i>Materials Science and Engineering</i> , Vol. B17, pp. 47-67 (1993).			
ZE	CE	Heyns, M.M., et al., "New Wet Cleaning Strategies for Obtaining Highly Reliable Thin Oxides." <i>MRP Symposium Proceedings on Materials Research Society</i> , Spring Meeting, San Francisco, CA, Apr. 12-13, p. 35 (1993).			

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ZE	CF	Huynh, C., et al., "Plasma versus ozone photoresist ashing: Temperature effects on process-induced mobile ion contamination." <i>J. Vac. Sci. Technol.</i> , B9(2):353-356 (Mar./Apr. 1991).				
	CG	Isagawa, T., et al., "Ultra Clean Surface Preparation Using Ozonized Ultrapure Water." <i>Extended Abstracts of the 1992 Int'l. Conf. on Solid State Devices and Materials</i> ; pp. 193-195 (1992).				
	CH	Kasi, S., et al., "Surface Hydrocarbon Removal from Si by UV/Ozone." <i>ECS Extended Abstracts</i> , No. 458, pp. 691-692 (1990).				
	CI	Kasi, S., et al., "Vapor phase hydrocarbon removal for Si processing." <i>Appl. Phys. Lett.</i> , 57(20):2095-2097 (Nov. 1990).				
	CJ	Kern, W., "The Evolution of Silicon Wafer Cleaning Technology." <i>J. Electrochem. Soc.</i> , 137(6):1887-1892 (Jun. 1990).				
	CK	Krusell, W.C., et al., "Cleaning Technologies for High Volume Production of Silicon Wafers." <i>ECS Proc. of the First Int'l. Symposium on Cleaning Technology in Semiconductor Device Mfg.</i> , pp. 23-32 (Oct. 1989).				
	CL	Krusell, W.C., et al., "The Characterization of Silicon Substrate Cleaning Treatments by use of SIMS and MOS Electrical Testing." <i>ECS Extended Abstracts</i> , No. 229, p. 331-332 (1986).				
	CM	Nelson, S., "Ozonated water for photoresist removal." <i>Solid State Technology</i> , p. 107-112 (Jul. 1999).				
	CN	Ohmi, T., et al., "Native Oxide Growth and Organic Impurity Removal on Si Surface with Ozone-Injected Ultrapure Water." <i>J. Electrochem. Soc.</i> , 140(3):804-810 (Mar. 1993).				
	CO	Sehested, K., et al., "Decomposition of Ozone in Aqueous Acetic Acid Solutions (pH 0-4)." <i>J. Phys. Chem.</i> , pp. 1005-1009 (1992).				
ZE	CP	Shimada, H., et al., "Residual-Surfactant-Free Photoresist Development Process." <i>J. Electrochem. Soc.</i> , 139(6):1721-1730 (Jun. 1992).				

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Z E	CQ	Suemitsu, M., et al., "Low Temperature Silicon Surface Cleaning by HF Etching/Ultraviolet Ozone Cleaning (HF/UVOC) Method (I)-Optimization of the HF Treatment." <i>Japanese Journal of Applied Physics</i> , 28(12):2421-2424 (Dec. 1989).				X
	CR	Tabe, M., "UV ozone cleaning of silicon substrates in silicon molecular beam epitaxy." <i>Appl. Phys. Lett.</i> , 45(10):1073-1075 (Nov. 1984).				
	CS	Tong, J., et al., "Aqueous Ozone Cleaning of Silicon Wafers." <i>ECS Extended Abstracts</i> , Phoenix, AZ, Abstract No. 506, pp. 753 (Oct. 13-17, 1991).				
	CT	Tong, J., et al., "Aqueous Ozone Cleaning of Silicon Wafers." <i>Proc. of 2.sup.nd Int'l. Symposium on Cleaning Tech. In Semiconductor Device Mfg.</i> , pp. 18-25 (Oct. 1992).				
	CU	Vig, J., "UV/Ozone Cleaning of Surfaces." <i>U.S. Army Elec. Tech. and Devices Lab.</i> , pp. 1-26.				
	CV	Vig, J., "UV/Ozone Cleaning of Surfaces: A Review." <i>Surface Contamination: Genesis, Detection, and Control</i> , pp. 235-253 (1979).				
	CW	Vig, J., et al., "UV/Ozone Cleaning of Surfaces." <i>IEEE Transactions on Parts, Hybrids, and Packaging</i> , Vol. PHP-12(4):365-370 (Dec. 1976).				
	CX	Vig, J., "UV/Ozone Cleaning of Surfaces." <i>U.S. Army Electronics Technology and Devices Laboratory</i> , ERADCOM, Ft. Monmouth, NJ, 07703-5302, pp. 1027-1034 (Sep./Oct. 1984).				
	CY	Zafonte, L., et al., "UV/Ozone Cleaning For Organics Removal on Silicon Wafers." <i>SPIE Optical Microlithography III: Technology for the Next Decade</i> , 470:164-175 (1984).				
	CZ	Zazzera, L.A., et al., "XPS and SIMS Study of Anhydrous HF and UV/Ozone-Modified Silicon (100) Surfaces." <i>J. Electrochem. Soc.</i> , 136(2):484-491 (Feb. 1989).				
	DA	"Ozone Concentration Measurement in a Process Gas." <i>Proposed IOA Pan American Group Guideline</i> , pp. 1-21 (Dec. 1993).				
Z E	DB	"Ozone for Semiconductor Applications." <i>Sorbios</i> , pp. 1-6 (Oct. 1991).				

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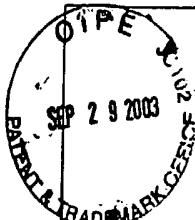
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